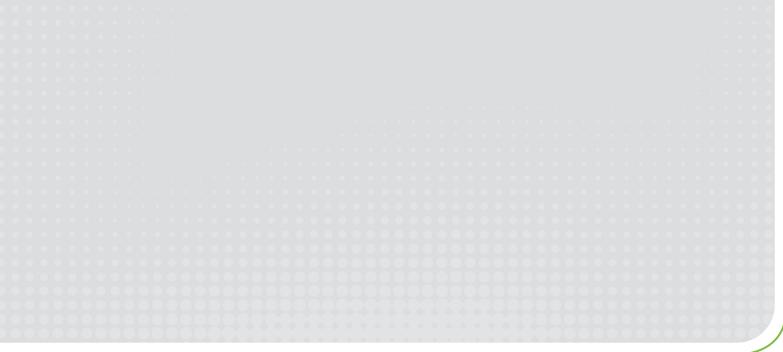


ETHERCAT[®] PRODUCT SELECTION GUIDE NEW STANDARDS IN PERFORMANCE & FLEXIBILITY





ETHERCAT® PRODUCT SELECTION GUIDE

AUTOMATION & CONTROL



MicroNode[™] Combo Programmable Automation Controller

- Each MicroNode module supports 16 DIO
- Each module supports 16-bit, 8 analog inputs, 4 analog outputs, ±10V



HyperPAC

Programmable Industrial PC

- Ease of fieldbus protocols integration with IIoT solution
- Compact form factor
- Robust IPC
- Flexible configuration

Custom Automation

- Customizable architecture allows for expansion, customization, and modularity
- Remote boxes can add I/O connections in remote locations
- Supports hardwired safety interlocks or software programmable safety interlocks (TUV SIL3)

mks

P Series





G Series

Mass Flow Controllers and Meters

- Full Scale flow rates from 5 sccm to 300 slm
- Proven, patented thermal sensor and mechanical design
- Multi-range/multi-gas capability; 1% of set point accuracy



G Series

Pressure Controllers

- Pressure control for Full Scale from 500 Torr to 100 psia
- Thermally stable pressure sensor for 1% of set point accuracy
- Digital flow control algorithm for fast response to set point

P Series

ETG.5003.2025

Pressure Controllers

- Pressure control for Full Scale from 10 to 1000 Torr
- Thermally stable pressure sensor for 1% of set point accuracy
- Flow meter option for backside wafer pressure control applications

ETG.5003.2025

P Series

Dual Zone Pressure Controller

- Pressure control for Full Scale for 20, 50 or 100 Torr
- Integrated mass flow meter
- Full Scale flow measurement range for 20, 50, 100 sccm

FLOW/GAS DELIVERY



Delta™

Flow Ratio Controllers

- Accurate and repeatable flow ratio control for better process optimization
- For use in cascade configurations
- Operates to temperatures up to 60°C ambient

PLASMA SOURCES



HA-MFV

High Accuracy In-Situ Mass Flow Verifier

- Flow rates up to 3000 sccm
- External volume insensitivity
- Reading measurement accuracy of 1.0% or better



Paragon®

Remote Plasma Sources

- For high gas dissociation rates (>98%) of NF₃
- Gas flows up to 8 slm and pressures up to 10 Torr
- Compatible with O2 and NF₃ mixed gases



R*evolution®

Remote Plasma Sources

- Up to 6kW of plasma power
- Integrated, self-contained unit for on-chamber installation
- Quartz plasma applicator, high density for oxygen species

CM12P1

ETG.5003.201X

Remote Plasma Source

mks

- 12kW of plasma power
- Compatible with NF₃, O₂, N₂, and Ar
- Meets Semi F47 immunity response requirements

CH24P1

mks

- 24kW of plasma power
- Supports high flow applications
- Split power train for flexible installation

ETG.5003.201X

Remote Plasma Source

ETHERCAT® PRODUCT SELECTION GUIDE

PRESSURE/VACUUM MEASUREMENT



901P

Load Lock Transducer

- Designed specifically for semiconductor load lock applications
- Providing medium vacuum measurement and atmospheric switching
- Fast and accurate pressure measurement for improved cycle time and particle reduction



902B

Vacuum Transducer

- 1000 Torr Full Scale range
- Piezo resistive diaphragm sensor
- Stainless steel diaphragm



925 MicroPirani[™] Vacuum Transducer

- MEMS-based technologies, including MicroPirani[™] technology
- Applicable for foreline and general vacuum measurement applications
- Fast and accurate pressure measurement



972B DualMag[™] **Cold Cathode Transducer**

- Single transducer with wide pressure measurement range from atmosphere to ultra-high vacuum
- MEMS-based MicroPirani technology combined with cold cathode ionization technology
- Small footprint design



DA03B

Baratron[®] Capacitance Manometer

- Heated at 150°C to 200°C
- Optional internallymounted solid state process relays
- Compact design



DA05A Baratron[®] Capacitance

Manometer • Ambient operating

- temperature at 60°C
- 0.1 and 0.25 Torr Full Scale ranges
- Standard sensor or etch/ fluorine/deposition-friendly sensor option

DA06A

ETG.5003.2080

Baratron[®] Capacitance Manometer

- Heated at 45°C, 80°C, 100°C
- 1 Torr to 1 mTorr Full Scale ranges
- Standard sensor or fluorine/deposition-friendly sensor option

ETG.5003.2080

DA07A

Baratron[®] Capacitance Manometer

- Unheated or heated at 45°C, 80°C, 100°C
- 1 Torr to 1000 Torr Full Scale ranges
- Standard sensor or etch/ flourine/deposition-friendly sensor option

PRESSURE/VACUUM MEASUREMENT



390 Micro-Ion® Vacuum Transducer

- Combined Micro-Ion[®] ionization gauge technology, Conductron heat loss sensor, and 2 Piezo resistive sensors
- Continuous pressure measurement from high vacuum to atmosphere

SENSING SOLUTIONS



TEMPERATURE CONVERTER Multichannel

- 3 5 channels
- ±0.1°C (2σ) stability
- 0.01°C resolution



392 Micro-Ion® Vacuum Transducer

- -----
- Combined Micro-Ion[®] ionization gauge technology with a miniature Pirani Conductron heat-loss sensor
- Dual ionization gauge filaments

VALVES

T2BA

Exhaust Throttle Valve

- Advanced model-based pressure control algorithm
- High-speed configurations available (<250 msec. open to close)
- Selectable high torque drives with soft-sealing available

ETHERCAT[®] PRODUCT SELECTION GUIDE

Product	Mailbox Service	Synchronization	Firmware
Automation & Control			
MicroNode [™] Combo Programmable Automation Controller HyperPAC Programmable Industrial PC	• CoE • FoE	Free RunDC EventSM Event to 500 usec	Yes
Flow			
G Series Mass Flow Controllers & Meters G Series Pressure Controllers	• CoE • FoE	Free RunSM2	Yes
P Series Pressure Controllers P Series Dual Zone Pressure Controllers Delta™ Flow Ratio Controllers	• CoE • FoE	Free RunSM2	Via FoE
HA-MFV Insitu Mass Flow Verifier	• CoE • FoE	Free RunSM3	Via FoE
Pressure/Vacuum Measurement			
901P Load Lock Transducer 902B Vacuum Transducer 925 MicroPirani Vacuum Transducer 972B DualMag [™] Cold Cathode Transducer 390 Micro-Ion [®] Vacuum Transducer 392 Micro-Ion [®] Vacuum Transducer	• CoE • FoE	SM Event	EtherCATTransducer
DA03B Baratron® Capacitance Manometer DA05A Baratron® Capacitance Manometer DA06A Baratron® Capacitance Manometer DA07A Baratron® Capacitance Manometer	• CoE • FoE	Free Run	Yes
Sensing Solution			
Temperature Converter	CoE	Free Run	EtherCAT
Valves			
T2BA Exhaust Throttle Valve	• CoE • FoE	Free Run (to loop update)DC EventSM Event	• Via FoE • Via Web GU

Product		Synchronization	Monitor Parameters
Plasma Sources			
	Paragon [®] Remote Plasma Sources Revolution [®] Remote Plasma Sources CM12P1 Remote Plasma Source CH24P1 Remote Plasma Source	Free Run	 Power Run Time / Ignition Time Faults AC/DC Line System Ready Internal Device Temperature

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MKS Corporate Headquarters

2 Tech Drive Andover, MA 01810 +1 978-645-5500 +1 800-227-8766 (in USA) **MKS INC.** enables technologies that transform our world. We deliver foundational technology solutions to leading edge semiconductor manufacturing, electronics and packaging, and specialty industrial applications.

We apply our broad science and engineering capabilities to create instruments, subsystems, systems, process control solutions and specialty chemicals technology that improve process performance, optimize productivity and enable unique innovations for many of the world's leading technology and industrial companies.

Our solutions are critical to addressing the challenges of miniaturization and complexity in advanced device manufacturing by enabling increased power, speed, feature enhancement, and optimized connectivity. Our solutions are also critical to addressing ever-increasing performance requirements across a wide array of specialty industrial applications.

Additional information can be found at www.MKS.com.

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